



IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: KANG et al.

Attorney Docket No.:
LAM1P177/P1139

Application No.: 10/648,953

Examiner: MALDONADO, Julio J.

Filed: August 26, 2003

Group: 2823

Title: REDUCTION OF FEATURE CRITICAL
DIMENSIONS

Confirmation No.: 4068

11/17/2005 MWOLDGE1 00000037 10648953

01 FC:1806

180.00 DP

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on November 14, 2005 in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA, 22313-1450.

Signed: _____

Sue Funchess
Sue Funchess

**INFORMATION DISCLOSURE STATEMENT
BEFORE FINAL ACTION OR NOTICE OF ALLOWANCE
(37 CFR §§ 1.56 AND 1.97(c))**

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, a copy of which is attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is being filed after the mailing date of the first Office Action on the merits, or after three months of the filing date of this application, whichever event occurred last, but it is believed before the mailing date of either: (i) a final action under §1.113 or (ii) a notice of allowance under §1.311, whichever occurs first.

Accompanying this Information Disclosure Statement is

☐ a statement as specified in 37 CFR 1.97(e); or

☒ the fee set forth in 37 CFR 1.17(p).

[37 CFR §1.97(e) Statement, if relied upon]

The undersigned hereby states:

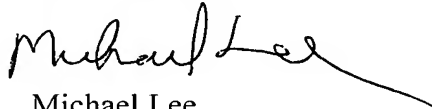
☐ that each item of information contained in the Information Disclosure Statement was first cited in a communication from a foreign patent office in a counterpart foreign application no more than three months prior to the filing of the Information Disclosure Statement; or

☐ that no item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the Information Disclosure Statement was known to any individual designated in § 1.56(c) more than three months prior to the filing of the Information Disclosure Statement.

If fees are due, enclosed is our Check No. 28203 for \$180.00 in payment of the Information Disclosure Statement Fee. If it is determined that any additional fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 50-0388 (Order No. LAM1P177).

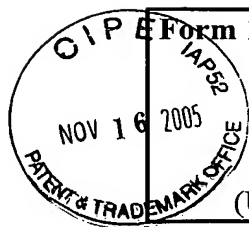
Respectfully submitted,

BEYER WEAVER & THOMAS, LLP



Michael Lee
Registration No. 31,846

P.O. Box 70250
Oakland, CA 94612-0250
Telephone: (650) 961-8300



Form 1449 (Modified)

**Information Disclosure
Statement By Applicant**

(Use Several Sheets if Necessary)

Atty Docket No.
LAM1P177/P1139

Applicant:
KANG et al.

Filing Date
August 26, 2003

Application No.:
10/648,953

Group
2811

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1.						
	A2.						
	A3.						
	A4.						
	A5.						
	A6.						
	A7.						
	A8.						
	A9.						
	A10.						

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1.							
	B2.							
	B3.							
	B4.							
	B5.							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1.	U.S. Application No. 11/016,455, entitled "Reduction of Etch Mask Feature Critical Dimensions", by inventors Huang et al., filed 12/16/04.
	C2.	U.S. Application No. 11/208,098, entitled "Etch Features with Reduced Line Edge Roughness", by inventors Sadjadi et al., filed 08/18/05.
	C3.	
	C4.	

Examiner	Date Considered
----------	-----------------

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.